CHEMICAL VAPOR DEPOSITION OF POROUS SILICON CARBIDE ONTO CERAMIC MICROSPHERES USING A FLUIDIZED BED REACTOR

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To Mom and Dad, who instilled in me the value of an education and have supported me though all of mine.

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ABSTRACT

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The Gas Fast Reactor (GFR) program in the United States requires novel nuclear fuel materials to achieve the fuel performance requirements for a fast neutron spectrum at high temperatures. Previous studies have shown that uranium carbide coated with a porous silicon carbide (SiC) layer and a dense SiC layer performs well in GFR conditions. A known process for coating the fuel is to suspend the microspheres in a fluidized bed (FB) reactor, flow a combination of gases over the particles to produce SiC on the surface of the particles through chemical vapor deposition (CVD). This thesis focuses on the use of methylsilane (CH₃SiH₃) as a SiC precursor, the experiment built at Purdue University's Fuel Cycle and Materials Laboratory (FCML) to test it, and the results of that experiment.

The experiment utilized two designs for a fluidized bed that resulted in eleven coating runs. Of these coating runs, the last three demonstrated that a porous and a denser layer of SiC deposited on ceramic microspheres may be produced from a fluidized bed reactor using methylsilane gas. These experiments were conducted at 1200° C and 900° C, where the porous layer is deposited at 1200° C and the denser layer is deposited at 900° C. The last three coating runs used a total deposition time of one hour, three hours, and five hours and resulted in coating thicknesses of $3.58 \pm 0.32 \mu m$, $10.18 \pm 1.68 \mu m$, and 95.32

 \pm 1.03µm respectively. The deposition rate for this system is approximately 0.05µ/min for 900°C and 0.06 µ/min for 1200°C.